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Suetsugu et al.

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(54) **NEGATIVE TYPE RESIST COMPOSITION**

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(58) Field of Search 430/270.1, 921

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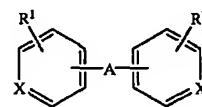
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(57) **ABSTRACT**

A negative type resist composition is provided, which provides excellent resolution, satisfactory profile and outstanding process stability; is suitable for exposure using deep ultra violet ray; and comprises alkali soluble resin, acid generator, crosslinking agent, and a basic compound represented by the following formula (I)



wherein, A represents bivalent aliphatic hydrocarbon residue which may be optionally interrupted by imino group, sulfide group, or disulfide group, X represents nitrogen atom or C(NH₂), and R¹ and R² independently represent hydrogen or alkyl.

13 Claims, No Drawings